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	Application No.	10/540,056
INFORMATION DISCLOSURE	Filing Date	June 22, 2005
STATEMENT BY APPLICANT	First Named Inventor	Sato et al.
OTATEMENT BY ALL EIGANT	Art Unit	1795
(Multiple sheets used when necessary)	Examiner	John S Y Chu
SHEET 1 OF 1	Attorney Docket No.	SHIGA7.021APC

			U.S. PATENT	DOCUMENTS	
Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear

			FOREIGN PATI	ENT DOCUMENTS		
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	1	JP 2004-012513	01-15-2004	Matsushita Elec. Ind. Co., Ltd.		4
	2	JP 2002-373845	12-26-2002	Sony Corp.		v/
	3	EP 1357428	10-29-2003	Murakami et al.		

NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	Τ1	
	4	UTSUMI, "Low-energy E-Beam Proximity Lithography (LEEPL): Is the Simplest the Best?", Japanese Journal of Applied Physics, Vol. 38, Part 1, No. 12B, pp. 7046-7051 (1999)		
	5	Decision to Grant a Patent issued on August 26, 2008 on the counterpart Japanese Application No. 2003-334029 of the related Application No. 10/572,709.		

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ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /JSC/

Examiner Signature /John Chu/ Date Considered 11/24/2008

*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.